

	Hits	Search Text	DBs
1	524	ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
2	853	ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped)	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
3	131	ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
4	920	ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type))	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
5	175	((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)) and fluorine CF4 "CF sub 4" and chlorine HCl CL2 "Cl sub 2")	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
6	52	((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)) and fluorine CF4 "CF sub 4" and chlorine HCl CL2 "Cl sub 2") and etch\$3 same fluorine CF4 "CF sub 4" same chlorine HCl CL2 "Cl sub 2") and fluorine CF4 "CF sub 4" near chlorine HCl CL2 "Cl sub 2")	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
7	107	((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)) and fluorine CF4 "CF sub 4" and chlorine HCl CL2 "Cl sub 2") and etch\$3 same fluorine CF4 "CF sub 4" same chlorine HCl CL2 "Cl sub 2")	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
8	55	((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)) and fluorine CF4 "CF sub 4" and chlorine HCl CL2 "Cl sub 2") and etch\$3 same fluorine CF4 "CF sub 4" same chlorine HCl CL2 "Cl sub 2") and fluorine CF4 "CF sub 4" near chlorine HCl CL2 "Cl sub 2")	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
9	45	((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)) and fluorine CF4 "CF sub 4" and chlorine HCl CL2 "Cl sub 2") and etch\$3 same fluorine CF4 "CF sub 4" same chlorine HCl CL2 "Cl sub 2") and clear\$3	USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM TCB
		((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)) and fluorine CF4 "CF sub 4" and chlorine HCl CL2 "Cl sub 2")	
10	27	CL2 "Cl sub 2") and near\$3 and ((ETCHS3 and ("S-Me" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (si silicon polysilicon doped) ((ETCHS3 and ("SAME" EQUAL EQUIVALENT SIMILAR CLOSE) NEAR (RATE SPEED))) and ETCHS3 near (dopos \$2type)) and fluorine CF4 "CF sub 4" and chlorine HCl CL2 "Cl sub 2") and etch\$3 same fluorine CF4 "CF sub 4" same chlorine HCl CL2 "Cl sub 2") and fluorine CF4 "CF sub 4" near chlorine HCl CL2 "Cl sub 2")	US-PGPUB, EPO, JPO, DERWENT, IBM TCB

